

Cryogenic Small-Signal Model for 0.55- μm Gate-Length Ion-Implanted GaAs MESFET's

J. Laskar, J. Kruse and M. Feng. "Cryogenic Small-Signal Model for 0.55- μm Gate-Length Ion-Implanted GaAs MESFET's." 1992 Microwave and Guided Wave Letters 2.6 (Jun. 1992 [MGWL]): 242-244.

The cryogenic microwave performance of 0.5 x 300 μm gate ion-implanted GaAs MESFET's are presented. The devices studied here have been fabricated as part of a process control monitor chip (PCM) which uses comparable industry standard design rules. We have performed detailed small-signal element modeling to determine the temperature dependence of important physical parameters over a lattice temperature range from 300 K to 115 K. We find appreciable improvement in cut-off frequency and well behaved temperature dependence of transconductance ($g_{\text{sub m/}}$) and gate-source capacitance ($C_{\text{sub gs/}}$). Empirical relations for the temperature dependence of $f_{\text{sub T/}}$, $f_{\text{sub max/}}$, $g_{\text{sub m/}}$, and $C_{\text{sub gs/}}$ that should provide accurate temperature dependant device and circuit models, are presented.

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